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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/665,275	09/22/2003	Koichi Wago	146712004300	5466
25227	7590	06/06/2006		
MORRISON & FOERSTER LLP 1650 TYSONS BOULEVARD SUITE 300 MCLEAN, VA 22102			EXAMINER ANGEBRANNDT, MARTIN J	
			ART UNIT 1756	PAPER NUMBER

DATE MAILED: 06/06/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

<b>Office Action Summary</b>	<b>Application No.</b>	<b>Applicant(s)</b>	
	10/665,275	WAGO, KOICHI	
	<b>Examiner</b>	<b>Art Unit</b>	
	Martin J. Angebranndt	1756	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --  
**Period for Reply**

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

**Status**

1) Responsive to communication(s) filed on 9/22/03 & 4/28/06.  
 2a) This action is **FINAL**.                            2b) This action is non-final.  
 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

**Disposition of Claims**

4) Claim(s) 1-19 is/are pending in the application.  
 4a) Of the above claim(s) 8-19 is/are withdrawn from consideration.  
 5) Claim(s) \_\_\_\_\_ is/are allowed.  
 6) Claim(s) 1-7 is/are rejected.  
 7) Claim(s) \_\_\_\_\_ is/are objected to.  
 8) Claim(s) 1-19 are subject to restriction and/or election requirement.

**Application Papers**

9) The specification is objected to by the Examiner.  
 10) The drawing(s) filed on \_\_\_\_\_ is/are: a) accepted or b) objected to by the Examiner.  
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  
 Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).  
 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

**Priority under 35 U.S.C. § 119**

12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).  
 a) All    b) Some \* c) None of:  
 1. Certified copies of the priority documents have been received.  
 2. Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.  
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

\* See the attached detailed Office action for a list of the certified copies not received.

**Attachment(s)**

1) Notice of References Cited (PTO-892)  
 2) Notice of Draftsperson's Patent Drawing Review (PTO-948)  
 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)  
 Paper No(s)/Mail Date 9/22/03.

4) Interview Summary (PTO-413)  
 Paper No(s)/Mail Date. \_\_\_\_\_.  
 5) Notice of Informal Patent Application (PTO-152)  
 6) Other: \_\_\_\_\_.

1. The response of the applicant to the restriction requirement has been received and made of record.
2. Restriction to one of the following inventions is required under 35 U.S.C. 121:
  - I. Claims 1-7, drawn to an interference exposure apparatus, classified in class 359, subclass 35.
  - II. Claims 8-10, drawn to a master magnetic disk, classified in class 360, subclass 135.
  - III. Claims 11-15, drawn to a photolithographic process for forming a magnetic master, classified in class 430, subclass 320.
  - IV. Claims 16-19, drawn to using a metal contact master for magnetic contact printing, classified in class 360, subclass 17.

The inventions are distinct, each from the other because of the following reasons:

3. Inventions group I and group II are related as apparatus and product made. The inventions in this relationship are distinct if either or both of the following can be shown: (1) that the apparatus as claimed is not an obvious apparatus for making the product and the apparatus can be used for making a materially different product or (2) that the product as claimed can be made by another and materially different apparatus (MPEP § 806.05(g)). In this case the master may be made using convention photolithographic (non-interferometric) processes or electron beam lithography.
4. Inventions group I and group III are related as product and process of use. The inventions can be shown to be distinct if either or both of the following can be shown: (1) the process for using the product as claimed can be practiced with another materially different

product or (2) the product as claimed can be used in a materially different process of using that product. See MPEP § 806.05(h). In the instant case the process does not require a rotary stage and the apparatus can be used to form other grating patterns, such as hologons/optical scanning discs and an embossing master for replicating these in polymers/resins.

5. Inventions group I and group IV are unrelated. Inventions are unrelated if it can be shown that they are not disclosed as capable of use together and they have different designs, modes of operation, and effects (MPEP § 802.01 and § 806.06). In the instant case, the different inventions the processes and apparatus of the groups are not related and incapable of being used together/simultaneously.

6. Inventions group III and group II are related as process of making and product made. The inventions are distinct if either or both of the following can be shown: (1) that the process as claimed can be used to make another and materially different product or (2) that the product as claimed can be made by another and materially different process (MPEP § 806.05(f)). In the instant case the master may be made using convention photolithographic (non-interferometric) processes or electron beam lithography.

7. Inventions group II and group IV are related as product and process of use. The inventions can be shown to be distinct if either or both of the following can be shown: (1) the process for using the product as claimed can be practiced with another materially different product or (2) the product as claimed can be used in a materially different process of using that product. See MPEP § 806.05(h). In the instant case the master can be used as an embossing master for replicating patterns in polymers/resins. (ie no magnetic field need be applied)

8. Inventions group III and group IV are unrelated. Inventions are unrelated if it can be shown that they are not disclosed as capable of use together and they have different designs, modes of operation, and effects (MPEP § 802.01 and § 806.06). In the instant case, the processes of the groups are not related and incapable of being used together/simultaneously.

9. Because these inventions are independent or distinct for the reasons given above and have acquired a separate status in the art in view of their different classification and because of their recognized divergent subject matter, restriction for examination purposes as indicated is proper.

10. A telephone call was made to Raj Dave' on March 21, 2006 to request an oral election to the above restriction requirement, but did not result in an election being made.

Applicant is advised that the reply to this requirement to be complete must include (i) an election of a species or invention to be examined even though the requirement be traversed (37 CFR 1.143) and (ii) identification of the claims encompassing the elected invention.

The election of an invention or species may be made with or without traverse. To reserve a right to petition, the election must be made with traverse. If the reply does not distinctly and specifically point out supposed errors in the restriction requirement, the election shall be treated as an election without traverse.

Should applicant traverse on the ground that the inventions or species are not patentably distinct, applicant should submit evidence or identify such evidence now of record showing the inventions or species to be obvious variants or clearly admit on the record that this is the case. In either instance, if the examiner finds one of the inventions unpatentable over the prior art, the evidence or admission may be used in a rejection under 35 U.S.C.103(a) of the other invention.

11. Applicant's election without traverse of group I in the reply filed on 04/28/2006 is acknowledged.

Claims 8-19 are withdrawn.

12. New corrected drawings in compliance with 37 CFR 1.121(d) are required in this application because The details cannot be seen. Applicant is advised to employ the services of a competent patent draftsperson outside the Office, as the U.S. Patent and Trademark Office no longer prepares new drawings. The corrected drawings are required in reply to the Office action to avoid abandonment of the application. The requirement for corrected drawings will not be held in abeyance.

The details of figure 3 and 4 cannot be resolved. The applicant may wish to introduce a higher quality version of these figures in place of those of record. If the applicant decides on a photograph, then a petition is necessary.

13. The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

14. Claims 1-4 and 6-7 are rejected under 35 U.S.C. 112, first paragraph, because the specification, while being enabling for interferometric devices including a laser, does not reasonably provide enablement for exposure processes other than those using lasers. The specification does not enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to practice the invention commensurate in scope with these claims.

The applicant discloses a two arm interferometric exposure device. By its nature, the coherence length of the light source must be long to maintain the phase relationship of the beams/arms and lasers are the only light sources with a sufficiently long coherence length.

Please move the limitation of claim 5 into independent claim 1.

15. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

- (a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.
- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

16. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

17. Claims 1,2 and 4-6 are rejected under 35 U.S.C. 102(b) as being fully anticipated by Sakai et al. JP 58-094149.

Sakai et al. JP 58-094149 teaches with respect to figure 3, a laser the beam of which is divided into parts using a beams splitter (6), two mirrors (7a,7b) are used to reflect the sub-beams, so they overlap and they are expanded in diameter using (8a,8b) to fill the aperture field of the slit in the mask (12) and the holder (11) is rotated to form concentric circles in the resist

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coated substrate (10) as shown in figure 1. The formula describing the fringe period as a function of wavelength and angle of separation of the beams appears in the lower left hand column of page 2. The pitches appear to be in the range of 0.1 to 10 microns (page 2, upper right column).

The examiner notes that when the plane of the beams is oriented in the radial direction, the fringes will be oriented to form concentric circles, rather than the radially extending lines usually formed for holgons. (as in Debesis '443)

18. Claims 1,2 and 4-6 are rejected under 35 U.S.C. 102(b) as being fully anticipated by Sakai JP 01-315048.

Sakai JP 01-315048 teach with respect to figure 3, a laser the beam of which is divided into parts using a beams splitter (6), two mirrors (7a,7b) are used to reflect the sub-beams, so they overlap and they are expanded in diameter using (8a,8b) to fill the aperture field of the slit in the mask (12) and the holder (11) is rotated to form concentric circles in the resist coated substrate (10) as shown in figure 1. The formula describing the fringe period as a function of wavelength and angle of separation of the beams appears in the upper right hand column of page 3. The pitches appear to be in the range of 0.1 to 10 microns (page 2, lower left column).

19. Claims 1,2 and 4-7 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sakai et al. JP 58-094149, further in view of Funato et al. '852.

Funato et al. '852 teach the formula describing the fringe period as a function of wavelength and angle of separation of the beams (formula 17). The use of a HeCd laser (441.6 nm) as the recording laser to form the pattern in the resist is disclosed. (5/62-68).

Sakai et al. JP 58-094149 does not describe a particular wavelength, which is dominant force in defining the pitch or feature size. It would have been obvious to one skilled in the art to modify the apparatus of Sakai et al. JP 58-094149 by using blue/UV lasers known to be useful in forming grating patterns in photosensitive materials, such as the 441.6 nm HeCd lasers, which can form features with pitches of as small as ~220.8 nm with a reasonable expectation of forming a useful tracking/servo groove or pattern.

20. Claims 1-7 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sakai et al. JP 58-094149, in view of Anderson et al. '385.

Anderson et al. '385 teach the formula describing the fringe period as a function of wavelength and angle of separation of the beams (1/25). The use of an Argon Ion laser (351 nm) as the recording laser to form the pattern in the resist is disclosed. (2/60-66). The phase shifter (19) in figure 1 , is disclosed as enabling active stabilization of the fringes for increased accuracy in the fringes formed (2/67-3/25, 3/43-59, 4/55-5/12).

Sakai et al. JP 58-094149 does not describe a particular wavelength, which is dominant force in defining the pitch or feature size. It would have been obvious to one skilled in the art to modify the apparatus of Sakai et al. JP 58-094149 by using blue/UV lasers known to be useful in forming grating patterns in photosensitive materials, such as the 351 nm Ar ion laser, which can form features with pitches of as small as ~175 nm and with the phase shifter able to provide increased stabilization of the fringes as taught by Anderson et al. '385 with a reasonable expectation of forming a useful tracking/servo groove or pattern.

The use of the shorter wavelength laser and the ability to stabilize the fringes, provides additional support for the inherent ability to form the fringes with a small pitch (below 350 nm) with the increased accuracy due to the fringe stabilization.

21. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

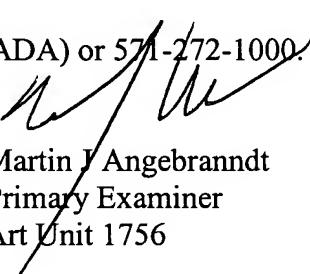
Andrews '646, Carlson '395, Ishikawa '062, and Ih '105 teach the formation of hologon scanners.

Stepanov et al. WO 99/63371 teaches phase control in holographic exposure processes. "Holographically generated high resolution track servo pattern for optical or capacitive readout", IBM Tech Discl. Bull., Vol. 26(6) pp. 2951-2952 (11/1983) teaches fine servo patterns comprising concentric parallel lines.

22. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Martin J. Angebranndt whose telephone number is 571-272-1378. The examiner can normally be reached on Monday-Thursday and alternate Fridays.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark Huff can be reached on 571-272-1385. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.



Martin J Angebranndt  
Primary Examiner  
Art Unit 1756

06/02/2006